

(SYLLABUS)

1.

(Course Title)		(Instructor)			
(Year)	2023	(Semester)	1	(Course No.)	2150084001
(Class)	01	(Open to)		(Course Classification)	-
(Credit)	3.0		00		100
(Office)		(Telephone)	0426	(e-mail)	hoh@ssu.ac.kr
	(PBL)		+		
	(*) (ABEEK Classification)			(*) (ABEEK Requirement)	
(Course Description)	CMOS , FINFET, EUV DRAM , 3D NAND				

가	(100)	(100%)
	100	30
	100	40
	100	20
	100	10

(Required Texts)		* /Silicon VLSI Technology/James D. Plummer/PrenticeHall/2000
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2.

(Week)	(Keyword)	(Description)		(Texts)
01		-		
02		- BJT , CMOS		
03	Active region formation	- Thermal oxidation, Photolithography ,		
04	N- and P-well,	- Dopant Diffusion, Thin Film deposition , 가 (high-k)		
05	gate formation	-		
06	LDD formation	- Ion Implantation, Etching		
07	Source drain formation	- 가		
08	Contact and interconnections	- Back-End technology,		
09		- PBL , ,		
10		- (SOI),		
11		- Back-End technology		
12	FINFET multi-gate device	- FINFET 3 ,		
13	EUV	- EUV ,		
14	DRAM	- DRAM ,		
15	3D NAND	- 3D NAND ,		

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3. ()

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	Open-ended problem		
	Teamwork		
	Communication skills		